

ELAST (10720910 SDANTOON Enfert word

\$510: (1) 10/614052 \$511: (0) "6812119".pn.

5 512: (62503) (SRAM static adj3 memory static adj RAM)

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U*#	Inventor	Document ID	Issue P		Title		Curran C	Current X	Ratrieva S	CP				lmage Do	2				
		20040099885	2004 1	CMOS SRAM	cell configure	d using mu	257/20		. 2	1 2	, 2	7:1	10	US 20040	,		4	100	
2 r r	Fried, Davi U	20030102518	2003 2	Finfet SRAM c	ell using low	mobility pla	257/40 2	57/350;	- 53	0.0	10	7	r	US 20030	4				
3 1 1	Nowak; Ed U:	6794718 82	2004 1	High mobility o	rystaline pla	nes in dou	257/34 4	38/149;	S	1	b.	c r	16	US 67947				× 11	
4 rr	Fried; Davi U	6684582 82	2003 1	Fin memory co	and metho	d of fabrice :	257/30 2	57/310:	P	5 2	2		-	US 66645					
5 oc	Nowak; Ed U	6610578 B2	2003 3	Method for for	ming asymm	etric dual g	438/30 2	57/E21.4	33	rr	S.	r: r	.0	US 66105					
6	Yeo, Yee-CU	20050035415	2005 1	Multiple-gate t	ransistors fo	med on buil	257/40 4	38/283	8	CC	r	rr	18	US 20050					
7	Yeo, Yee-CU	20040266077	2004 1	Structure and	method for fe	oming the	438/15		ρ	FF	E :	rr	T.	US 20040	200				
8 S C C	Lee, Jong- U	20040256647	2004 3	Strained silicon	n finFET dev	ice	257/28		19	rc	C	ri ic	. C	US 20040					
9r r	Boyanov, B U	20040253774	2004 1	Double-gate tr	ansistor with	enhanced 4	438/17 4	38/268		rr		rir	۳	US 20040	Mil. 3	111	# #	1.16	
10 mm r:	Pham, Dani U	20040219722	2004 1	METHOD FOR	FORMING A	DOUBLE-	138/15 2	57/401;	: 2	C	15	r ir	15	US 20040					
Art Ocea	(Stark)																		